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NGB特許部

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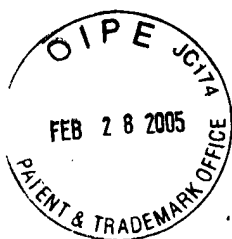
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富士フイルム(吉)

: 10955613954

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## PATENT APPLICATION

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of:

Kunihiko Kodama

Group Art Unit 1752

Appln. No.: 10/668,348

Examiner: LEE, SIN J

Filed: September 24, 2003

For: PHOTORESISTIVE COMPOSITION AND ACID GENERATOR

DECLARATION UNDER 37 C.F.R. §1.132Assistant Commissioner for Patents  
Alexandria, VA 22313-1450

Sir:

I, Kunihiko Kodama, do declare and state as follows:

I am a citizen of Japan.

I graduated from Hiroshima University and received a Master's Degree in Faculty of Science, Course in Chemistry (Organic Chemistry) in March 1994.

Since April 1994 I have been employed by Fuji Photo Film Co., Ltd. and have been engaged in research and development of photoresist materials for semiconductors at the Yoshida-Minami Factory Research Division of said company.

I am an inventor of the invention described and claimed in the above-named application, and I am familiar with the subject matter disclosed by said application as well as the Office Action dated November 29, 2004 concerning said application.

In order to demonstrate the unexpected superiority of the present invention, the following experimentation was conducted by me or under my supervision.

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PATENT APPLICATION

EXPERIMENTATION

Resist solution for Comparative Example A1 was prepared in the same manner as in Example 1 of the present application except for using Compound (I-27) of Aoi (JP 2002-255930) as a acid generator. The resist solution was coated and dried to form a resist film in the same manner as in Example 1 of the present application. The resist film was evaluated on Sensitivity and Profile in the same manner as in Example 1 of the present application. The result is shown in Table A1 below together with the result of Example 1 of the present application.

TABLE A1

	Acid generator	Sensitivity (mJ/cm <sup>2</sup> )	Profile
Comparative Example A1 (Aoi)	(I-27): Aoi	19	A (Rectangular shape)
Example 1	(I-1)*	14	A (Rectangular shape)

\*: Acid generator (I-1) is described in the present application.

As is clear from the results of Table A1, the present invention is not anticipated by Aoi, and is not obvious from the cited reference.

I declare further that all statements made herein of my own knowledge are true and that all statements made on information and belief are believed to be true; and further that these statements were made with the knowledge that willful

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## PATENT APPLICATION

false statements and the like so made are punishable by fine or imprisonment, or both, under §1001 of Title 18 of the United States Code and that such willful false statements may jeopardize the validity of the application or any patent issuing thereon.

Respectively submitted,

Date: Feb 25 2005Kunihiko Kodama

Kunihiko Kodama

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